

Amendments to the Specification:

After the title and before the first paragraph, please insert the following paragraph:

THIS APPLICATION IS A U.S. NATIONAL PHASE APPLICATION OF PCT INTERNATIONAL APPLICATION PCT/JP2004/004901.

Please replace the paragraph, beginning at page 15, line 11, with the following rewritten paragraph:

The effect of the present invention is also achievable with other types of deposition equipment 30: for example, deposition equipment with a buffer space between chambers for adjusting tact time, those with a chamber for heating or cooling, or those adopting a batch system for substrate holder 30-1 in the deposition chamber. Even if the deposition equipment is configured with a batch-type substrate holder 1 in the chamber, the same effect is achievable by adopting the aforementioned structure for substrate holder 1 holding substrate 13.